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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/671,864	09/29/2003	Ralph Kurt	081468-0306164	8185

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EXAMINER

CHACKO DAVIS, DABORAH

ART UNIT PAPER NUMBER

1756

DATE MAILED: 09/16/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/671,864

Applicant(s)

KURT ET AL.

Examiner

Daborah Chacko-Davis

Art Unit

1756

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 29 September 2003.
2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-20 is/are pending in the application.
4a) Of the above claim(s) _____ is/are withdrawn from consideration.
5) ☐ Claim(s) _____ is/are allowed.
6) ☒ Claim(s) 1-20 is/are rejected.
7) ☐ Claim(s) _____ is/are objected to.
8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) ☒ All b) ☐ Some * c) ☐ None of:
1. ☒ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3) ☒ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date 09/03.
4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____.
5) ☐ Notice of Informal Patent Application (PTO-152)
6) ☐ Other: _____.

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

2. Claims 1-4, 8-17, and 19-20, are rejected under 35 U.S.C. 102(e) as being anticipated by U. S. Patent No. 6,737,358 (He et al, hereinafter referred to as He).

He, in col 2, lines 1-53, in col 3, lines 64-67, in col 4, lines 1-11, and lines 62-67, in col 5, lines 1-10, discloses a system with an illumination source to illuminate a lithographic mask (patterning device) to generate a lithographic pattern (patterned illumination beam) on the resist-coated substrate, wherein the system includes plasma gases such as CF₄ , etc., and inactive gases such as nitrogen, argon and facilitator gases such as oxygen; the gases in the lithographic system are activated (activation device) by an RF source in order to generate a plasma of the corresponding gases introduced into the system (claims 1-4, 8-17, and 19-20).

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

Art Unit: 1756

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

4. Claims 1, 4, 12-20, are rejected under 35 U.S.C. 102(b) as being anticipated by U. S. Patent No. 6,225,032 (Hasegawa et al).

Hasegawa, in the abstract, in col 3, lines 60-67, in col 4, lines 1-67, in col 5, lines 58-67, in col 6, lines 47-67, in col 7, lines 1-13, and lines 38-67, in col 8, lines 1-24, in col 11, lines 10-39, in col 12, lines 4-19, discloses a lithographic system comprising an irradiation source that irradiates a resin blank (resist coated substrate) through a mask, wherein the laser beam irradiates gaseous molecules of tetrafluoromethane (positioned near the discharge port) in the chamber; the CF₄ gases are irradiated with ArF laser (EUV source, the activating device) so as to activate the fluorine containing substance (claims 1, 4, 12-17, and 19-20). Hasegawa, in col 9, lines 9-60, discloses that the fluorine-containing compound is encapsulated in a microporous media (sponge) (claim 18).

Claim Rejections - 35 USC § 103

5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

6. Claims 5-6, are rejected under 35 U.S.C. 103(a) as being unpatentable over U. S. Patent No. 6,737,358 (He et al, hereinafter referred to as He) in view of Journal of

Art Unit: 1756

Crystal growth 222 (2001) 452-458 (McGinnis et al, herein after referred to as McGinnis).

He is discussed in paragraph no. 2.

The difference between the claims and He is that He does not disclose that the one or more compounds include one or more nitrogen hydrides (claim 5). He does not disclose that the one or more compounds includes at least one of ammonia, diazine, hydrazine, and salts thereof (claim 6).

McGinnis, on page 452-453, discloses that the ammonia flux is introduced into the plasma atmosphere prior to exposing the substrate.

Therefore, it would be obvious to a skilled artisan to modify He by replacing the nitrogen plasma atmosphere with ammonia because McGinnis, in the abstract, discloses that the ammonia flux introduced into the plasma beam resulted in the inhibition of surface roughening and produced a relatively smooth substrate surface.

7. Claim 7, is rejected under 35 U.S.C. 103(a) as being unpatentable over U. S. Patent No. 6,737,358 (He et al, hereinafter referred to as He) in view of U. S. Patent No. 5,320,707 (Kanekiyo et al, hereinafter referred to as Kanekiyo).

He is discussed in paragraph no. 2.

The difference between the claims and He is that He does not disclose that the one or more compounds include nitric acid (claim 7).

Kanekiyo, in col 23, lines 65-68, discloses that the nitric acid is introduced into the plasma to perform passivation processing on the laminate layers.

Art Unit: 1756

Therefore, it would be obvious to a skilled artisan to modify He by replacing the nitrogen plasma atmosphere with nitric acid because Kanekiyo, in col 23, lines 65-68, and in col 24, lines 1-2, discloses that nitric acid passivation enables the removal of residues on the laminate layer prior to development (washing processing).

Conclusion

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

dcd

September 10, 2005



JOHN A. MCPHERSON
PRIMARY EXAMINER